

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	3561	positive adj3 composition	US-PGPUB; USPAT	OR	ON	2005/03/28 15:53
L2	0	(disufonium or trisulfonium) same conjugat\$	US-PGPUB; USPAT	OR	ON	2005/03/28 15:55
L3	11	disufonium or trisulfonium	US-PGPUB; USPAT	OR	ON	2005/03/28 16:01
L4	0	1 and 3	US-PGPUB; USPAT	OR	ON	2005/03/28 16:01
L5	148468	conjugat\$	US-PGPUB; USPAT	OR	ON	2005/03/28 16:02
L6	340	1 and 5	US-PGPUB; USPAT	OR	ON	2005/03/28 16:03
L7	790414	positive	US-PGPUB; USPAT	OR	ON	2005/03/28 16:03
L8	11	3 and 7	US-PGPUB; USPAT	OR	ON	2005/03/28 16:07
L9	340	6 and 7	US-PGPUB; USPAT	OR	ON	2005/03/28 16:07

Day : Monday
Date: 3/28/2005

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Inventor Name Search Result

Your Search was:

Last Name = TAKAHASHI

First Name = HYOU

Application#	Patent#	Status	Date Filed	Title	Inventor Name
10319493	Not Issued	120	12/16/2002	NEGATIVE RESIST COMPOSITION	TAKAHASHI, HYOU
10361505	Not Issued	041	02/11/2003	RESIST COMPOSITION FOR ELECTRON BEAM, EUV OR X-RAY	TAKAHASHI, HYOU
10606845	Not Issued	071	06/27/2003	RESIST COMPOSITION	TAKAHASHI, HYOU
10613044	Not Issued	071	07/07/2003	RESIST COMPOSITION	TAKAHASHI, HYOU
10634954	Not Issued	041	08/06/2003	POSITIVE RESIST COMPOSITION	TAKAHASHI, HYOU
10654942	Not Issued	094	09/05/2003	RESIST COMPOSITION	TAKAHASHI, HYOU
10799864	Not Issued	030	03/15/2004	STIMULUS SENSITIVE COMPOUND AND STIMULUS SENSITIVE COMPOSITION CONTAINING THE SAME	TAKAHASHI, HYOU
10863347	Not Issued	030	06/09/2004	POSITIVE-WORKING RESIST COMPOSITION	TAKAHASHI, HYOU
10942852	Not Issued	041	09/17/2004	POSITIVE RESIST COMPOSITION AND PATTERN FORMATION METHOD USING THE SAME	TAKAHASHI, HYOU
10958346	Not Issued	030	10/06/2004	POSITIVE RESIST COMPOSITION AND PATTERN FORMING METHOD USING THE SAME	TAKAHASHI, HYOU
11050721	Not Issued	030	02/07/2005	RESIST COMPOSITION FOR IMMERSION EXPOSURE AND PATTERN FORMATION METHOD USING THE SAME	TAKAHASHI, HYOU

Inventor Search Completed: No Records to Display.

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Inventor Name Search Result

Your Search was:

Last Name = YASUNAMI

First Name = SHOICHIRO

Application#	Patent#	Status	Date Filed	Title	Inventor Name
07534902	Not Issued	166	06/08/1990	SILVER HALIDE PHOTOGRAPHIC MATERIALS AND METHOD FOR MANUFACTURE THEREOF	YASUNAMI, SHOICHIRO
07547552	5108885	150	07/03/1990	SILVER HALIDE PHOTOGRAPHIC MATERIAL CONTAINING CROSS LINKED POLYMER SAME	YASUNAMI, SHOICHIRO
07548646	Not Issued	166	07/05/1990	SILVER HALIDE PHOTOGRAPHIC MATERIAL AND METHOD OF PRODUCING THE SAME	YASUNAMI, SHOICHIRO
07652759	5237031	150	02/08/1991	ORGANIC SOLID ELECTROLYTE	YASUNAMI, SHOICHIRO
07742497	5153115	150	08/05/1991	SILVER HALIDE PHOTOGRAPHIC MATERIALS AND METHOD FOR MANUFACTURE THEREOF	YASUNAMI, SHOICHIRO
07935336	5250409	150	08/27/1992	SILVER HALIDE PHOTOGRAPHIC MATERIAL	YASUNAMI, SHOICHIRO
08042169	5350648	150	04/02/1993	NONAQUEOUS SECONDARY BATTERY	YASUNAMI, SHOICHIRO
08085173	5340672	150	07/02/1993	SECONDARY BATTERY	YASUNAMI, SHOICHIRO
08562223	5686203	150	11/28/1995	NON-AQUEOUS SECONDARY BATTERY	YASUNAMI, SHOICHIRO
08814961	5707756	150	03/10/1997	NON-AQUEOUS SECONDARY BATTERY	YASUNAMI, SHOICHIRO
08860804	6001139	150	07/10/1997	NONAQUEOUS SECONDARY BATTERY HAVING MULTIPLE-LAYERED	YASUNAMI, SHOICHIRO

				NEGATIVE ELECTRODE	
<u>08959439</u>	Not Issued	161	10/28/1997	NON-AQUEOUS SECONDARY BATTERY	YASUNAMI, SHOICHIRO
<u>09125146</u>	<u>6371995</u>	150	08/11/1998	NONAQUEOUS SECONDARY BATTERY AND METHOD FOR PREPARING SAME	YASUNAMI, SHOICHIRO
<u>09493285</u>	<u>6270941</u>	150	01/28/2000	POSITIVE SILICONE- CONTAINING PHOTOSENSITIVE COMPOSITION	YASUNAMI, SHOICHIRO
<u>09496259</u>	<u>6296985</u>	150	02/01/2000	POSITIVE PHOTORESIST COMPOSITION COMPRISING A POLYSILOXANE	YASUNAMI, SHOICHIRO
<u>09671177</u>	<u>6387590</u>	150	09/28/2000	POSITIVE PHOTORESIST COMPOSITION	YASUNAMI, SHOICHIRO
<u>09698190</u>	<u>6589705</u>	150	10/30/2000	POSITIVE-WORKING PHOTORESIST COMPOSITION	YASUNAMI, SHOICHIRO
<u>09729178</u>	<u>6346363</u>	150	12/05/2000	POSITIVE PHOTORESIST COMPOSITION	YASUNAMI, SHOICHIRO
<u>09826850</u>	<u>6555289</u>	150	04/06/2001	POSITIVE PHOTORESIST COMPOSITION	YASUNAMI, SHOICHIRO
<u>09880030</u>	<u>6696219</u>	150	06/14/2001	POSITIVE RESIST LAMINATE	YASUNAMI, SHOICHIRO
<u>09961281</u>	<u>6852467</u>	150	09/25/2001	POSITIVE RESIST COMPOSITION	YASUNAMI, SHOICHIRO
<u>10020958</u>	<u>6479213</u>	150	12/19/2001	POSITIVE PHOTORESIST COMPOSITION	YASUNAMI, SHOICHIRO
<u>10101178</u>	Not Issued	094	03/20/2002	NEGATIVE-WORKING RESIST COMPOSITION FOR ELECTRON BEAMS OR X- RAYS	YASUNAMI, SHOICHIRO
<u>10118896</u>	<u>6777161</u>	150	04/10/2002	LOWER LAYER RESIST COMPOSITION FOR SILICON- CONTAINING TWO-LAYER RESIST	YASUNAMI, SHOICHIRO
<u>10120551</u>	Not Issued	061	04/12/2002	RESIST COMPOSITION	YASUNAMI, SHOICHIRO
<u>10274386</u>	<u>6773862</u>	150	10/21/2002	NEGATIVE RESIST COMPOSITION	YASUNAMI, SHOICHIRO
<u>10319493</u>	Not Issued	120	12/16/2002	NEGATIVE RESIST COMPOSITION	YASUNAMI, SHOICHIRO
<u>10330332</u>	Not Issued	041	12/30/2002	NEGATIVE RESIST COMPOSITION	YASUNAMI, SHOICHIRO

10396583	6746813	150	03/26/2003	NEGATIVE RESIST COMPOSITION	YASUNAMI, SHOICHIRO
10606845	Not Issued	071	06/27/2003	RESIST COMPOSITION	YASUNAMI, SHOICHIRO
10613044	Not Issued	071	07/07/2003	RESIST COMPOSITION	YASUNAMI, SHOICHIRO
10634954	Not Issued	041	08/06/2003	POSITIVE RESIST COMPOSITION	YASUNAMI, SHOICHIRO
10642291	Not Issued	041	08/18/2003	NEGATIVE RESIST COMPOSITION	YASUNAMI, SHOICHIRO
10654942	Not Issued	094	09/05/2003	RESIST COMPOSITION	YASUNAMI, SHOICHIRO
10791559	Not Issued	030	03/03/2004	POSITIVE WORKING RESIST COMPOSITION	YASUNAMI, SHOICHIRO
10812074	Not Issued	030	03/30/2004	POSITIVE RESIST COMPOSITION	YASUNAMI, SHOICHIRO
10812092	Not Issued	041	03/30/2004	POSITIVE RESIST COMPOSITION	YASUNAMI, SHOICHIRO
10840624	Not Issued	030	05/07/2004	POSITIVE RESIST COMPOSITION	YASUNAMI, SHOICHIRO
10941822	Not Issued	030	09/16/2004	POSITIVE RESIST COMPOSITION AND PATTERN-FORMING METHOD USING THE SAME	YASUNAMI, SHOICHIRO
10941925	Not Issued	040	09/16/2004	POSITIVE RESIST COMPOSITION AND PROCESS FOR FORMING PATTERN USING THE SAME	YASUNAMI, SHOICHIRO

Inventor Search Completed: No Records to Display.

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
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Inventor Name Search Result

Your Search was:

Last Name = MIZUTANI

First Name = KAZUYOSHI

Application#	Patent#	Status	Date Filed	Title	Inventor Name
<u>07550446</u>	<u>5216105</u>	150	07/10/1990	NEW SILOXANE POLYMERS AND POSITIVE WORKING LIGHT-SENSITIVE COMPOSITIONS COMPRISING THE SAME	MIZUTANI, KAZUYOSHI
<u>07555599</u>	<u>5143816</u>	150	07/23/1990	LIGHT-SENSITIVE COMPOSITION COMPRISING A POLYSILOXANE AND A NAPHTHOQUINONE DIAZIDE	MIZUTANI, KAZUYOSHI
<u>07647067</u>	<u>5141840</u>	150	01/29/1991	LIGHT-SENSITIVE COMPOSITION CONTAINING ONION SALT AND POLYSILOXANE REACTION PRODUCT	MIZUTANI, KAZUYOSHI
<u>07936644</u>	<u>5252686</u>	150	08/28/1992	SILOXANE POLYMERS AND POSITIVE WORKING LIGHT-SENSITIVE COMPOSITIONS COMPRISING THE SAME	MIZUTANI, KAZUYOSHI
<u>07936788</u>	<u>5338640</u>	150	08/28/1992	SILOXANE POLYMERS AND POSITIVE WORKING LIGHT-SENSITIVE COMPOSITIONS COMPRISING THE SAME	MIZUTANI, KAZUYOSHI
<u>08003465</u>	<u>5276124</u>	150	01/12/1993	NEW SILOXANE POLYMERS AND POSITIVE WORKING LIGHT-SENSITIVE COMPOSITIONS COMPRISING THE SAME	MIZUTANI, KAZUYOSHI
<u>08003501</u>	<u>5278273</u>	150	01/12/1993	NEW SILOXANE POLYMERS AND POSITIVE WORKING LIGHT-SENSITIVE COMPOSITIONS COMPRISING THE SAME	MIZUTANI, KAZUYOSHI
<u>08269040</u>	<u>5488182</u>	150	06/30/1994	NOVEL PHENOL	MIZUTANI,

				COMPOUNDS CONTAINING METHOXYMETHYL GROUP OR HYDROXYMETHYL GROUP	KAZUYOSHI
<u>08296425</u>	<u>5460917</u>	150	08/26/1994	POSITIVE WORKING PHOTOSENSITIVE LITHOGRAPHIC PRINTING PLATE UTILIZING PHENOL DERIVATIVE COMPOUND CONTAINING PHOTOSENSITIVE COMPOSITION	MIZUTANI, KAZUYOSHI
<u>08691371</u>	<u>6132935</u>	150	08/02/1996	NEGATIVE-WORKING IMAGE RECORDING MATERIAL	MIZUTANI, KAZUYOSHI
<u>08908522</u>	<u>6090531</u>	150	08/07/1997	COMPOSITION FOR ANTI-REFLECTIVE COATING MATERIAL	MIZUTANI, KAZUYOSHI
<u>08997393</u>	<u>6165684</u>	150	12/23/1997	BOTTOM ANTI-REFLECTIVE COATING MATERIAL COMPOSITION AND METHOD FOR FORMING RESIST PATTERN USING THE SAME	MIZUTANI, KAZUYOSHI
<u>09397117</u>	<u>6399269</u>	150	09/16/1999	BOTTOM ANTI-REFLECTIVE COATING MATERIAL COMPOSITION FOR PHOTORESIST AND METHOD OF FORMING RESIST PATTERN USING THE SAME	MIZUTANI, KAZUYOSHI
<u>09496259</u>	<u>6296985</u>	150	02/01/2000	POSITIVE PHOTORESIST COMPOSITION COMPRISING A POLYSILOXANE	MIZUTANI, KAZUYOSHI
<u>09499703</u>	<u>6248500</u>	150	02/07/2000	COMPOSITION FOR ANTI-REFLECTIVE COATING MATERIAL	MIZUTANI, KAZUYOSHI
<u>09615708</u>	<u>6808869</u>	150	07/13/2000	BOTTOM ANTI-REFLECTIVE COATING MATERIAL COMPOSITION AND METHOD FOR FORMING RESIST PATTERN USING THE SAME	MIZUTANI, KAZUYOSHI
<u>09671177</u>	<u>6387590</u>	150	09/28/2000	POSITIVE PHOTORESIST COMPOSITION	MIZUTANI, KAZUYOSHI
<u>09698190</u>	<u>6589705</u>	150	10/30/2000	POSITIVE-WORKING PHOTORESIST COMPOSITION	MIZUTANI, KAZUYOSHI
<u>09698221</u>	<u>6506535</u>	150	10/30/2000	POSITIVE WORKING PHOTORESIST COMPOSITION	MIZUTANI, KAZUYOSHI

<u>09729178</u>	<u>6346363</u>	150	12/05/2000	POSITIVE PHOTORESIST COMPOSITION	MIZUTANI, KAZUYOSHI
<u>09826850</u>	<u>6555289</u>	150	04/06/2001	POSITIVE PHOTORESIST COMPOSITION	MIZUTANI, KAZUYOSHI
<u>09961281</u>	<u>6852467</u>	150	09/25/2001	POSITIVE RESIST COMPOSITION	MIZUTANI, KAZUYOSHI
<u>10020958</u>	<u>6479213</u>	150	12/19/2001	POSITIVE PHOTORESIST COMPOSITION	MIZUTANI, KAZUYOSHI
<u>10024358</u>	<u>6727040</u>	150	12/21/2001	POSITIVE RESIST COMPOSITION TO BE IRRADIATED WITH ONE OF AN ELECTRON BEAM AND X-RAY	MIZUTANI, KAZUYOSHI
<u>10099981</u>	Not Issued	083	03/19/2002	POSITIVE RESIST COMPOSITION	MIZUTANI, KAZUYOSHI
<u>10118896</u>	<u>6777161</u>	150	04/10/2002	LOWER LAYER RESIST COMPOSITION FOR SILICON-CONTAINING TWO-LAYER RESIST	MIZUTANI, KAZUYOSHI
<u>10156227</u>	<u>6743565</u>	150	05/29/2002	POSITIVE RESIST COMPOSITION WITH (BIS-TRI FLUOROMETHYL) METHYL SUBSTITUTED STYRENE	MIZUTANI, KAZUYOSHI
<u>10187291</u>	<u>6878502</u>	150	07/02/2002	POSITIVE RESIST COMPOSITION	MIZUTANI, KAZUYOSHI
<u>10247656</u>	<u>6830872</u>	150	09/20/2002	PLANOGRAPHIC PRINTING PLATE PRECURSOR PROVIDED WITH AN IMAGE FORMING LAYER CONTAINING A FLUORINE MACROMOLECULAR COMPOUND	MIZUTANI, KAZUYOSHI
<u>10317110</u>	Not Issued	041	12/12/2002	POSITIVE RESIST COMPOSITION	MIZUTANI, KAZUYOSHI
<u>10361505</u>	Not Issued	041	02/11/2003	RESIST COMPOSITION FOR ELECTRON BEAM, EUV OR X-RAY	MIZUTANI, KAZUYOSHI
<u>10372240</u>	<u>6811947</u>	150	02/25/2003	POSITIVE RESIST COMPOSITION	MIZUTANI, KAZUYOSHI
<u>10373170</u>	Not Issued	071	02/26/2003	PHOTOSENSITIVE RESIN COMPOSITION	MIZUTANI, KAZUYOSHI
<u>10378920</u>	Not Issued	041	03/05/2003	PHOTOSENSITIVE RESIN COMPOSITION	MIZUTANI, KAZUYOSHI
<u>10417209</u>	Not	071	04/17/2003	POSITIVE-WORKING RESIST	MIZUTANI,

	Issued			COMPOSITION	KAZUYOSHI
<u>10422789</u>	Not Issued	071	04/25/2003	POSITIVE RESIST COMPOSITION	MIZUTANI, KAZUYOSHI
<u>10448041</u>	Not Issued	092	05/30/2003	POSITIVE-WORKING RESIST COMPOSITION	MIZUTANI, KAZUYOSHI
<u>10455459</u>	Not Issued	040	06/06/2003	PHOTOSENSITIVE RESIN COMPOSITION	MIZUTANI, KAZUYOSHI
<u>10606845</u>	Not Issued	071	06/27/2003	RESIST COMPOSITION	MIZUTANI, KAZUYOSHI
<u>10613044</u>	Not Issued	071	07/07/2003	RESIST COMPOSITION	MIZUTANI, KAZUYOSHI
<u>10634954</u>	Not Issued	041	08/06/2003	POSITIVE RESIST COMPOSITION	MIZUTANI, KAZUYOSHI
<u>10642182</u>	6830871	150	08/18/2003	CHEMICAL AMPLIFICATION TYPE RESIST COMPOSITION	MIZUTANI, KAZUYOSHI
<u>10654942</u>	Not Issued	094	09/05/2003	RESIST COMPOSITION	MIZUTANI, KAZUYOSHI
<u>10791559</u>	Not Issued	030	03/03/2004	POSITIVE WORKING RESIST COMPOSITION	MIZUTANI, KAZUYOSHI
<u>10812092</u>	Not Issued	041	03/30/2004	POSITIVE RESIST COMPOSITION	MIZUTANI, KAZUYOSHI
<u>10840624</u>	Not Issued	030	05/07/2004	POSITIVE RESIST COMPOSITION	MIZUTANI, KAZUYOSHI
<u>10911510</u>	Not Issued	041	08/05/2004	POSITIVE RESIST COMPOSITION AND PATTERN FORMATION METHOD USING THE SAME	MIZUTANI, KAZUYOSHI
<u>10921962</u>	Not Issued	030	08/20/2004	POSITIVE PHOTORESIST COMPOSITION AND PATTERN MAKING METHOD USING THE SAME	MIZUTANI, KAZUYOSHI
<u>10929443</u>	Not Issued	030	08/31/2004	POSITIVE RESIST COMPOSITION AND PATTERN FORMATION METHOD USING THE SAME	MIZUTANI, KAZUYOSHI
<u>11060533</u>	Not Issued	020	02/18/2005	POSITIVE RESIST COMPOSITION AND PATTERN FORMING METHOD USING THE SAME	MIZUTANI, KAZUYOSHI

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